

What is claimed:

1. An automated computer-implemented method for a pre-layout estimation of a characteristic of a standard cell, said method comprising:

receiving a pre-layout representation of said standard cell;

applying at least one transformation to said pre-layout representation to obtain an estimated representation; and

characterizing said estimated representation to obtain said pre-layout estimation of said characteristic of said standard cell.

2. The method of claim 1, wherein said pre-layout representation is selected from the group consisting of: a spice netlist, a BDD-based transistor structure representation, and a pre-layout structural representation.

3. The method of claim 1, wherein a statistical pre-layout estimator is used to obtain said pre-layout estimation of said standard cell.

4. The method of claim 3, wherein said statistical pre-layout estimation of said standard cell is accurate to within about 5 percent of a post-layout timing characterization of a parasitic-dependent timing characteristic of said standard cell.

5. The method of claim 1, wherein a constructive estimator obtains said pre-layout estimation of said standard cell that is accurate to within about 1.5 percent of a post-layout timing characterization of a parasitic-dependent timing characteristic of said standard cell.

6. The method of claim 1, wherein said characteristic comprises a parasitic-dependent standard cell characteristic.

7. The method of claim 6, wherein said parasitic-dependent standard cell characteristic is selected from the group of standard cell characteristics consisting of: timing, power, input capacitance, noise, and any other parasitic-dependent standard cell characteristic.

8. The method of claim 1, wherein said at least one transformation is selected from the group consisting of: transistor folding, diffusion area and perimeter assigning of transistors of said standard cell, and adding wiring capacitances to said pre-layout representation.

9. The method of claim 8, wherein said transistor folding transformation is performed prior to said diffusion area and perimeter assigning of transistors of said standard cell transformation, and adding wiring capacitances to said pre-layout representation.

10. The method of claim 1, wherein said at least one transformation comprises assigning a diffusion area and a perimeter to transistors of said standard cell, wherein a diffusion region width, w , is estimated as $S_{pp}/2$ in the instance a net associated with said diffusion region is an intra-MTS net, and w is estimated as $W_c/2 + S_{pc}$ in the instance a net associated with said diffusion region is an inter-MTS net, wherein S_{pp} is a minimum poly-to-poly spacing, W_c is a contact width, and S_{pc} is a minimum poly-to-poly spacing.

11. The method of claim 1, wherein said at least one transformation comprises assigning a diffusion area and a perimeter to transistors of said standard cell, wherein a diffusion region width, w , is determined using a regression analysis estimation.

12. The method of claim 1, wherein said pre-layout representation is a pre-layout netlist and said at least one transformation comprises adding a wiring capacitance to each net in said pre-layout netlist, and a capacitance $C(n)$ of a net n is estimated as:

$$C(n) = \alpha \sum_{t \in TDS(n)} |MTS(t)| + \beta \sum_{t \in TG(n)} |MTS(t)| + \gamma$$

wherein α , β and γ are constants, $TDS(n)$ is a set of transistors whose drain or source is connected to a net n , $TG(n)$ is a set of transistors whose gate is connected to said net n and $MTS(t)$ is an MTS(Maximal Transistor Series) that includes a transistor.

13. The method of claim 12, wherein said constants α , β and γ are predetermined prior to said application of said at least one transformation to said pre-layout representation.

14. The method of claim 12, wherein said constants α , β and γ are determined by multiple regression analysis based on a representative set of laid out cells for a particular technology and cell architecture.

15. The method of claim 1, wherein said characteristic comprises a parasitic-dependent timing characteristic of said standard cell and said at least one transformation comprises diffusion area and perimeter assigning of transistors of said standard cell, and adding wiring capacitances to said pre-layout representation.

16. The method of claim 1, wherein said characteristic is selected from the group consisting of: a cell footprint and a pin placement of said cell.

17. A storage medium including computer readable program instructions for an automated computer-implemented method for obtaining a pre-layout estimation of a characteristic of a standard cell, said storage medium comprising:

program instructions for receiving a pre-layout representation of a standard cell;

program instructions for applying at least one transformation to said pre-layout representation to obtain an estimated representation; and

program instructions for characterizing said estimated representation to obtain said pre-layout estimation of said characteristic of said standard cell.

18. The storage medium of claim 17, wherein said pre-layout representation is selected from the group consisting of: a spice netlist, a BDD-based transistor structure representation, and a pre-layout structural representation.
19. The storage medium of claim 17, further comprising program instructions for a statistical estimator to obtain said pre-layout estimation of said standard cell.
20. The storage medium of claim 19, wherein said statistical pre-layout estimation of said standard cell is accurate to within about 5 percent of a post-layout timing characterization of a parasitic-dependent timing characteristic of said standard cell.
21. The storage medium of claim 17, wherein a constructive estimator obtains a pre-layout estimation of said standard cell that is accurate to within about 1.5 percent of a post-layout timing characterization of a parasitic-dependent timing characteristic of said standard cell.
22. The storage medium of claim 17, wherein said characteristic comprises a parasitic-dependent standard cell characteristic.
23. The storage medium of claim 22, wherein said parasitic-dependent standard cell characteristic is selected from the group of standard cell characteristics consisting of: timing, power, input capacitance, noise, and any other parasitic-dependent standard cell characteristic.
24. The storage medium of claim 16, wherein said at least one transformation is selected from the group consisting of: transistor folding, diffusion area and perimeter assigning of transistors of said standard cell, and adding wiring capacitances to said pre-layout representation.
25. The storage medium of claim 24, wherein said transistor folding transformation is performed, per program instructions, prior to said diffusion area and perimeter assigning of transistors of said standard cell transformation, and adding wiring capacitances to said pre-layout representation.

26. The storage medium of claim 17, wherein said at least one transformation comprises assigning a diffusion area and a perimeter to transistors of said standard cell, wherein a diffusion region width, w , is estimated as $S_{pp}/2$ in the instance a net associated with said diffusion region is an intra-MTS net, and w is estimated as $W_c/2 + S_{pc}$ in the instance a net associated with said diffusion region is an inter-MTS net, wherein S_{pp} is a minimum poly-to-poly spacing, W_c is a contact width, and S_{pc} is a minimum poly-to-poly spacing.

27. The method of claim 17, wherein said at least one transformation comprises assigning a diffusion area and a perimeter to transistors of said standard cell, wherein a diffusion region width, w , is determined using a regression analysis estimation.

28. The storage medium of claim 17, wherein said pre-layout representation is a pre-layout netlist and said at least one transformation comprises adding a wiring capacitance to each net in said pre-layout netlist, and a capacitance $C(n)$ of a net n is estimated as:

$$C(n) = \alpha \sum_{t \in TDS(n)} |MTS(t)| + \beta \sum_{t \in TG(n)} |MTS(t)| + \gamma$$

wherein α , β and γ are constants, $TDS(n)$ is a set of transistors whose drain or source is connected to a net n , $TG(n)$ is a set of transistors whose gate is connected to said net n and $MTS(t)$ is an MTS(Maximal Transistor Series) that includes a transistor.

29. The storage medium of claim 28, wherein said constants α , β and γ are predetermined prior to said application of said at least one transformation to said pre-layout representation.

30. The storage medium of claim 28, wherein said constants α , β and γ are determined by multiple regression analysis based on a representative set of laid out cells for a particular technology and cell architecture.

31. The storage medium of claim 17, wherein said characteristic comprises a parasitic-dependent timing characteristic of said standard cell and said at least one

transformation comprises diffusion area and perimeter assigning of transistors of said standard cell, and adding wiring capacitances to said pre-layout representation.

32. The storage medium of claim 17, wherein said characteristic is selected from the group consisting of: a cell footprint and a pin placement of said cell.